

**PHOTODEFINED INTEGRAL CAPACITOR WITH SELF-ALIGNED
DIELECTRIC AND ELECTRODES AND METHOD THEREFOR**

ABSTRACT OF THE DISCLOSURE

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A method for manufacturing a microelectronic assembly to have aligned conductive regions and dielectric regions, for example, for producing integral capacitors (32), generally entails providing a substrate (10) with a first conductive layer (12), forming a dielectric layer (14) on the first conductive layer, and then forming a second conductive layer on the dielectric layer (16).
10 A first region of the second conductive layer is then removed to expose a first region of the dielectric layer, which in turn is removed to expose a first region of the first conductive layer that is also removed. From this process, the first regions of the conductive and dielectric layers are each removed by using the
15 overlying layer or layers as a mask, so that the remaining second regions of these layers are coextensive.

